IN THE CLAIMS:

Please cancel claims 14-22, add claims 23-37, and amend the claims as follows:

1. (currently amended) An integrated bevel cleaning (IBC) apparatus, comprising:

a transfer position where a substrate is positioned ~~for processing and where a substrate is positioned after processing~~;

a rinse position where the substrate is rinsed; ~~and~~

an etch position where the ~~substrate~~ edge of the substrate ~~bead~~ is ~~removed~~ cleaned; ~~and~~

an actuator for positioning the substrate in the transfer position, the rinse position and the etch position; and

a plurality of cooperatively movable etchant dispense nozzles configured to dispense an etchant onto the front side and backside of the substrate.

2. (original) The IBC apparatus of claim 1 further comprising a substrate centering hoop for supporting the substrate in the transfer position.

3. (original) The IBC apparatus of claim 2 further comprising a substrate centering hoop rinsing nozzle.

4. (currently amended) The IBC apparatus of claim 1 further comprising at least one rinsing nozzle located proximate ~~said~~ the rinsing position for rinsing at least an edge region of the substrate.

5. (currently amended) The IBC apparatus of claim 4 wherein ~~said~~ the at least one rinsing nozzle ~~is~~ comprises a plurality of rinsing nozzles positioned to rinse ~~both sides~~ the front side and backside of the substrate.

6. (currently amended) The IBC apparatus of claim 1 ~~wherein said transfer position is accessible by~~ further comprising at least one slit valve located proximate the transfer position.

7. (currently amended) The IBC apparatus of claim 1 wherein ~~said~~ the actuator comprises a spindle assembly for retaining ~~a~~ the substrate and rotating the substrate, and a linear actuator for raising and lowering ~~said~~ the spindle assembly.

8. (currently amended) The IBC apparatus of claim 7 wherein ~~said~~ the spindle assembly comprises a vacuum chuck.

9. (currently amended) The IBC apparatus of claim 1 ~~further comprising~~ wherein the plurality of etchant dispense nozzles are coupled to at least one etchant ~~dispenser~~ dispensing arm assembly positioned proximate the etch position to apply etchant to the front side and backside of the substrate.

10. (currently amended) The IBC apparatus of claim 9 wherein ~~said~~ the etchant is applied to an edge exclusion zone of ~~said~~ the substrate.

11. (currently amended) The IBC apparatus of claim 9 wherein ~~said~~ the at least one etchant ~~dispenser~~ dispensing arm assembly is rotatable into a position near the substrate and away ~~form~~ from the substrate.

12. (currently amended) The IBC apparatus of claim 11 wherein ~~said~~ the at least one etchant ~~dispenser~~ dispensing arm assembly ~~is at least three~~ comprises a plurality of etchant ~~dispenser arms~~ dispensing arm assemblies.

13. (currently amended) The IBC apparatus of claim 12 wherein ~~said~~ the ~~at least three~~ plurality of etchant ~~dispenser arms~~ dispensing arm assemblies are cooperatively coupled ~~to a single motor~~ for simultaneously rotating the ~~at least three~~ plurality of etchant ~~dispenser arms~~ dispensing arm assemblies into a position near the substrate and away from the substrate.

14-22 (canceled)

23. (new) The IBC apparatus of claim 13 wherein the plurality of etchant dispensing arm assemblies are cooperatively coupled to a single motor for simultaneously rotating the plurality of etchant dispensing arm assemblies.

24. (new) An integrated bevel cleaning (IBC) apparatus, comprising:

a transfer position where a substrate is positioned;

a processing position wherein at least one of rinsing and etching is conducted on the substrate;

an actuator for positioning the substrate in the transfer position and the processing position; and

a plurality of cooperatively movable etchant dispense nozzles configured to dispense an etchant onto the front side and backside of the substrate.

25. (new) The IBC apparatus of claim 24 further comprising a substrate centering hoop for supporting the substrate in the transfer position.

26. (new) The IBC apparatus of claim 25 further comprising a substrate centering hoop rinsing nozzle.

27. (new) The IBC apparatus of claim 24 further comprising at least one rinsing nozzle located proximate the processing position for rinsing at least an edge region of the substrate.

28. (new) The IBC apparatus of claim 27 wherein the at least one rinsing nozzle comprises a plurality of rinsing nozzles positioned to rinse the front side and backside of the substrate.

29. (new) The IBC apparatus of claim 24 further comprising at least one slit valve located proximate the transfer position.

30. (new) The IBC apparatus of claim 24 wherein the actuator comprises a spindle assembly for retaining the substrate and rotating the substrate, and a linear actuator for raising and lowering the spindle assembly.

31. (new) The IBC apparatus of claim 30 wherein the spindle assembly comprises a vacuum chuck.

32. (new) The IBC apparatus of claim 24 wherein the plurality of etchant dispense nozzles are coupled to at least one etchant dispensing arm assembly positioned proximate the processing position to apply etchant to the front side and backside of the substrate.

33. (new) The IBC apparatus of claim 32 wherein the etchant is applied to an edge exclusion zone of the substrate.

34. (new) The IBC apparatus of claim 32 wherein the at least one etchant dispensing arm assembly is rotatable into a position near the substrate and away from the substrate.

35. (new) The IBC apparatus of claim 34 wherein the at least one etchant dispensing arm assembly comprises a plurality of etchant dispensing arm assemblies.

36. (new) The IBC apparatus of claim 35 wherein the plurality of etchant dispensing arm assemblies are cooperatively coupled for simultaneously rotating the plurality of etchant dispensing arm assemblies into a position near the substrate and away from the substrate.

37. (new) The IBC apparatus of claim 36 wherein the plurality of etchant dispensing arm assemblies are cooperatively coupled to a single motor for simultaneously rotating the plurality of etchant dispensing arm assemblies.